

What is claimed is:

1. A display device comprising:

signal lines which are formed on an upper surface side of a substrate;

wiring layers which are formed such that the wiring layers electrically connect one-side signal lines and another-side signal lines which define regions for forming terminal portions of the signal lines therebetween while obviating regions where the terminal portions of the signal lines are formed; and

an insulation film which has holes at regions forming the terminal portions and is formed so as to cover the signal lines and the wiring layer.

2. A display device comprising:

signal lines which are formed on an upper surface side of a substrate;

an insulation film which is formed such that the film covers the signal lines except for terminal portions of the signal lines; and

conductive layers which extend in the extension direction of the signal lines such that the conductive layers traverse the terminal portions, wherein

gaps are formed between respective sides of the conductive layer parallel to the extension direction of the conductive layer, and the insulation film and holes are formed in the signal lines at portions corresponding to the gaps along the extension

direction of the signal lines.

3. A display device according to claim 2, wherein the display region includes gate signal lines and drain signal lines, wherein a material of the signal lines is equal to a material of the gate signal lines, and a material of the conductive layers is equal to a material of the drain signal lines.

4. A display device according to claim 2, wherein gate signal lines, drain signal lines and interlayer insulation films which are formed between the respective signal lines are formed on a display region, and a material of the insulation films is identical with a material of the interlayer insulation film.

5. A display device comprising:

signal lines which are formed on an upper surface side of the substrate;

semiconductor layers which are formed below the signal lines by way of a first insulation film such that the semiconductor layers traverse the signal lines at terminal portions of the signal lines;

a second insulation film which is formed on the substrate such that the second insulation film also covers the signal lines and in which holes are formed at regions thereof where the semiconductor layers are formed; and

conductive layers which have respective sides thereof in the extension direction of the signal lines arranged at both sides of the signal lines and are connected with respective

semiconductor layers, wherein

the resistance of the semiconductor layers is lowered by introducing impurities thereinto using the signal lines as masks.

6. A display device according to claim 5, wherein the display region includes gate signal lines and drain signal lines, wherein a material of the signal lines is equal to a material of the gate signal lines, and a material of the conductive layers is equal to a material of the drain signal lines.

7. A display device according to claim 5, wherein the display region includes thin film transistors and a material of the semiconductor layers is equal to a material of semiconductor layers of the thin film transistors.

8. A display device according to claim 5, wherein the display region includes thin film transistors and a material of the first insulation film is equal to a material of gate insulation films of the thin film transistors.

9. A display device according to claim 5, wherein gate signal lines, drain signal lines and interlayer insulation films which are formed between the respective signal lines are formed on a display region and a material of the second insulation film is identical with a material of the interlayer insulation films.